OK TO ENTER: /HOH/

[10191/4116]

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor(s) : Franz LAERMER et al.

Serial No. : 10/524,610

Filed : August 11, 2005

For : LAYER SYSTEM HAVING A SILICON LAYER AND A

PASSIVATION LAYER, METHOD FOR CREATING A PASSIVATION LAYER ON A SILICON LAYER AND ITS

USE

Examiner : Hoang Ho

Art Unit : 2818
Confirmation No. : 9981

Mail Stop AF Commissioner for Patents P.O. Box 1450 Alexandria, Virginia 22313-1450

AMENDMENT UNDER 37 C.F.R. § 1.116

SIR

In response to the Final Office Action of August 2, 2010, for which the three-month response date expires on November 2, 2010, kindly amend the above-captioned application without prejudice as follows:

Amendments to the Claims are reflected in the listing of claims, which begins on page 2 of this paper.

Remarks begin on page 4 of this paper.